- density modulation [5].



$$i\hbar \frac{\partial \psi(x,t)}{\partial t} = -\frac{\hbar^2}{2m} \frac{\partial^2 \psi(x,t)}{\partial t^2} + \Phi(x,t)\psi(x,t)$$

here $\Phi(x,t) = \begin{cases} 0, & x < 0 \\ E_F + W - eF_0 x - eF_1 cos \omega tx, & x \ge 0 \end{cases}$
(a)
(b)
Pulsed laser field
 $F_1 cos(\omega_0 t)$
RF field $Acos(\omega_0 t)$
 F_1 being continuous wave (CW)
(b)
Pulsed laser field
 $F_1 e^{-\frac{t^2}{\sigma^2} cos(\omega_t)}$
RF field $Acos(\omega_0 t)$
 F_1 being Gaussian profile as $F_1 e^{-t^2/\sigma^2}$

$$D(\varepsilon) = \sum_{n=-\infty}^{\infty} w_n(\varepsilon),$$

$$J = e \int_0^\infty D(\varepsilon) N(\varepsilon) d\varepsilon,$$

[4] Zhou, Yang, and Peng Zhang. *Journal of Applied Physics* 130.6 (2021): 064902. [5] Gaertner, Georg., et al. Modern Developments in Vacuum Electron Sources. Germany: Springer, 2020.



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BEAM DENSITY MODULATION DURING EMISSION USING RF AND LASER FIELDS



- optical pulse.



> Pulsed photon/optical sources together with an RF field can produce sharp, highcurrent electron bunches with pulse duration comparable with or even less than that of the

> The emission current pulse amplitude, beam width (i.e., FWHM of the current pulse), and electron numbers per pulse, as well as the harmonic spectrum, are investigated in detail under various combinations of RF and optical fields.

